

REMARKS

Claims 2, 3, 5, 19 and 23-28 are pending. Claims 2, 3, 19 and 28 are amended.

Claim 2, 3, 5, 19 and 23-28 were rejected under 35 U.S.C. §112, second paragraph.

The Examiner states that there is insufficient antecedent basis for the semiconductor device in the preamble of claim 2.

According to the above-described amendments, "the semiconductor device" in the preamble of claim 2 is amended as --a semiconductor device--.

Claim 3 was rejected under 35 U.S.C. §112, second paragraph, as being incomplete for omitting essential steps.

According to the above-described amendments, it has become clear that the conductor pattern is formed over a first region of the semiconductor substrate, the fourth insulation film is formed over a side wall of the conductor pattern, and the first insulation film is etched to form the opening exposing in a part of a bottom thereof a second region of the semiconductor substrate, which is other than the first region, and exposing in another part of the bottom thereof the fourth insulation film. That is, the conductor pattern and the fourth insulation film are not formed in the second region of the semiconductor substrate.

Claim 19 was rejected under 35 U.S.C. §112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

"In the first step of etching the first insulation film" in claim 19 is a typographical error. According to the above-described amendments, "in the step of etching the first insulation film" is amended as --in the step of etching the third insulation film--.

Claim 28 was rejected under 35 U.S.C. §112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

According to the above-described amendments, it is clarified that "the first step" in claim 28 corresponds to "the first step of etching the third insulation film" in claim 2, and "the second step" in claim 28 corresponds to the second step of etching the second insulation film.

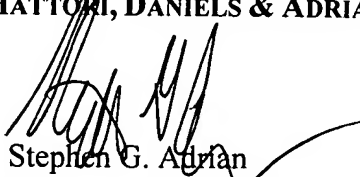
In view of the aforementioned amendments and accompanying remarks, Applicants submit that the claims, as herein amended, are in condition for allowance. Applicants request such action at an early date.

If the Examiner believes that this application is not now in condition for allowance, the Examiner is requested to contact Applicants' undersigned attorney to arrange for an interview to expedite the disposition of this case.

If this paper is not timely filed, Applicants respectfully petition for an appropriate extension of time. The fees for such an extension or any other fees that may be due with respect to this paper may be charged to Deposit Account No. 50-2866.

Respectfully submitted,

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